

Hard Coating is Because of Oppositely Worked Force-Energy Behaviors of Atoms

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Abstract –Coatings of specific materials in few atoms of thickness to several microns on certain substrate is the basic need of society and they attend the regular attention of scientific community working in different domains; decorative and protective coatings, transparent and insulating coatings, coating medical implants and surgical instruments, coatings for drug delivery and security purposes, ultra-precision machine coatings, coating cutting tools, coatings for MEMS and NEMS, and so on. Different coatings develop under significant composition of atoms where certain force-energy behaviors provide the provision for electrons (of gas atoms) to deal double clamping of energy knots of unfilled states (of solid atoms). Under certain process conditions, different nature atoms oppositely-switch force-energy behaviors to the ones originally owned where they locate common mid-points of their ground points at accommodating level resulting into deal binding. Because of adjusting contraction-expansion of clamping energy knots under varying potential energy of electrons, they develop structure of their atoms termed as hard coating, which is known since antiquity. Different properties and characteristics of hard coatings like hardness, adhesion, roughness and friction coefficient, etc. are emerged under attained mid-points of transformed atoms in evolving

structure. This work describes the science of depositing hard coating opening several new areas.

Keywords: Hard coating; TiN; Atomic nature; Expansion and contraction of clamping energy knot; Potential energy of electron; Ground point; Structure evolution

1. Introduction

Hard coatings are the integral part of scientific research along with technological advances. It is learnt routinely that marketable hard coatings for different usages are involved in different sorts of materials and deposition technique. In this context, several materials and their deposition techniques to deposit at suitable substrates and tools are available in the literature discussing and explaining both deposition history as well as application. In coatings, a minute deposited quantity of materials over less-important material solves the purpose of giving value-added results, often, in an astonishing way.

A variety of techniques are involved for depositing different sorts of hard coatings to suitable tools and substrates. Coatings were mainly employed with two targeted approaches; in the first case, the potential use of external coated part, which is not subjected to a great deal in the uncoated case and in the second case, potential use of internal surface where inner uncoated surface of material was not the subject of great concern but on coating, it became a great deal. Overall, coating the surface of certain material results into deliver its different behavior of functioning.

Atoms of electronic transition do not elongate and those belonging to inert gases split under the excess propagation of photons characteristic current through their certain flowing density [1]. Under attaining certain state behavior, atoms process heat energy to generate photon energy [2]. Depending on the nature of atoms dealing solid behavior, they evolve different basis-structures as per applicable format of force [3]. Formation of different tiny particles under varying conditions of the process reveals the information of registering different dynamics of their atoms [4]. A monolayer triangular-shaped tiny particle was developed under certain conditions which transformed one-dimensional arrays of atoms into structure of smooth elements under the joint application of surface format force and travelling photons of adequate wavelength [5]. Depending on the

atomic behavior of certain tiny-sized particles their role for nanomedicine can either be good or harmful [6]. At suitable precursor concentration, many tiny particles having certain geometry are developed [7]. Shape of tiny particles and particles are being controlled under the application of pulse behavior [8]. Particles of various anisotropic shapes developed in less than millisecond time [9]. Developing tiny particles of certain geometry is being tapped in silver solution and binary composition in addition to gold solution [10]. Predictor packing in developing gold particles is discussed elsewhere [11]. Different atomic behavior of carbon is being registered in tiny grains carbon films under Raman spectroscopy and energy loss spectroscopy [12]. Atomic structure and binding of carbon atoms is pinpointed [13]. Switching morphology-structure in carbon films is discussed elsewhere [14]. Under varying chamber pressure, a discernible change in the morphology and growth rate of carbon films is observed [15].

Depositing TiN coatings under varying process conditions on different substrates while employing a technique known as 'cathodic arc physical vapor deposition', a different morphology-structure along with hardness, surface roughness, friction coefficient, adhesion strength and overall performance of coated tools were resulted [16-27]. In addition to those, there are several other available studies in the literature targeting TiN hard coating along with processing technique and analysis [28-35]. In addition to TiN hard coating, studies on different types of hard coatings which were developed under various employed process conditions are also available [36-47]. The basic idea discussed in those studies is related to properties and characteristic of deposited coatings, which are subjected to the change of process parameters, type of material and processing approach, mainly.

The prosperous assembling of colloidal matter into meaningful structure will result into deal atoms and molecules as tomorrow's materials [48] and understanding in the individual dynamics of tiny-sized particles formation is essential before enabling the assembling to useful large-sized particles [49].

In addition to discussed scientific details of hard coatings, they are in the way to express relation between different atoms. This study reports the fundamental aspect of developing hard coatings at different substrates with emphasis on the formation of TiN

hard coating while depositing on a high-speed steel (HSS) disc in arc-based random physical vapor deposition technique. The aim of this work is to present the fundamental aspect of depositing hard coating, in general, and investigation about developing TiN coating deposited on HSS disc in random arc-based physical vapor deposition system.

2. Experimental details

Samples of HSS discs were utilized for the deposition of TiN coating in a commercially available coating unit known as 'cathodic arc physical vapor deposition', which can also be termed as 'random arc-based physical vapor deposition'. After necessary cleaning, the samples (diameter: 10 mm, thickness: 6 mm) were loaded in the coating system mark Hauzer Techno Coating (HTC) 625/2 ARC. The complete deposition procedure along with metallographic process of samples has been described earlier [27].

Surface morphology and interface studies were done using FE-SEM (Model LEO-1525). The thickness of the deposited coatings was measured by using FE-SEM under fracture cross-sectional image. Prior to go for TiN coating, an interlayer of Ti was deposited to gain and enhance the adhesion strength of the following coating, which is for time duration of 15 minutes. At start of depositing inter-layer, the chamber pressure was 5×10^{-6} mbar. While depositing inter-layer, a small amount of N gas flow rate (50 sccm) was being maintained by mass flow controller meter. To deposit TiN coating, substrate temperature was being maintained at 300°C where N gas flow rate was 250 sccm. The bias voltage was 50 volts where rotational speed of the substrate holder was set 60%. The current to ignite arc for ejecting Ti atoms from the metallic target was 100 amps. Total duration of the deposition was 90 minutes.

3. Results and discussion

Figure 1 (a) shows surface morphology of deposited TiN coating on HSS disc where coating surface is partially covered with macrodroplets (MDs) of size ranging from few microns to few hundred of nanometers, which are uniform in their distribution. A large sized macrodroplet (MD) in the central vicinity shows the mapping of the region where identifying the level of concentration of both sort of atoms is related to Ti and N

elements along with their scale of distribution. There are several studies dealing with the reduction of MDs under varying the process parameters along with different strategies [16-19, 22-24].

Figure 1 (b) shows fractured cross-sectional view of the coating where initially deposited Ti layer is observable having thickness less than one micron. Atoms of Ti interlayer first adhere to atoms of substrate because of their favorable nature to deal binding. Substrate surface where Ti interlayer adheres the elements W, Mo, Cr, V, C, Fe, etc. are involved as discussed elsewhere [16, 23], thus, they bound well to substrate surface by introducing the favorable conditions of forthcoming depositing TiN coating. In this context, the nature of substrate can deal different elements where their different force behaviors can introduce appreciable binding to depositing atoms, thus, governing value-added features of the resulted coating. Adhesion strength of TiN coating deposited under certain conditions in random arc-based PVD system is discussed elsewhere [25, 27].

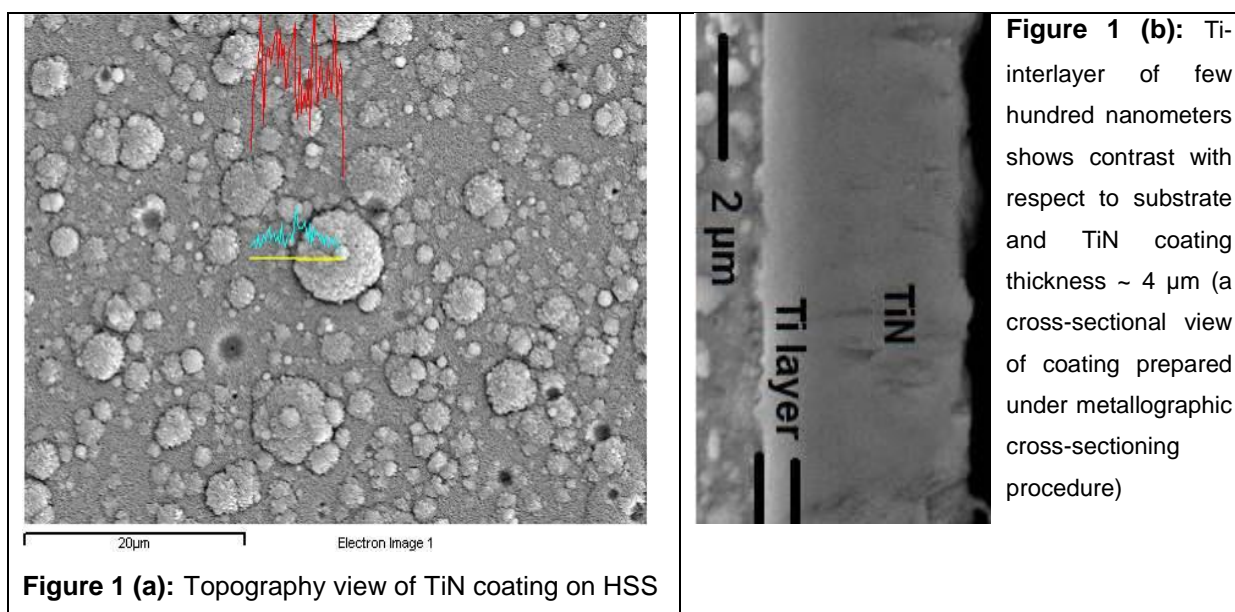


Figure 2 represents the mapping of Ti atoms present in TiN coating at point of MD shown in Figure 1 (a), which is presented in the form of histogram, which shows around 70% of content. This indicates that the area (volume) covered by Ti atoms in the TiN

coating at top front surface not only contained 70% of content of metallic element but it is also distributed densely in MD and in uniform manner. This indicates that that MD contained very less concentration of N atoms.

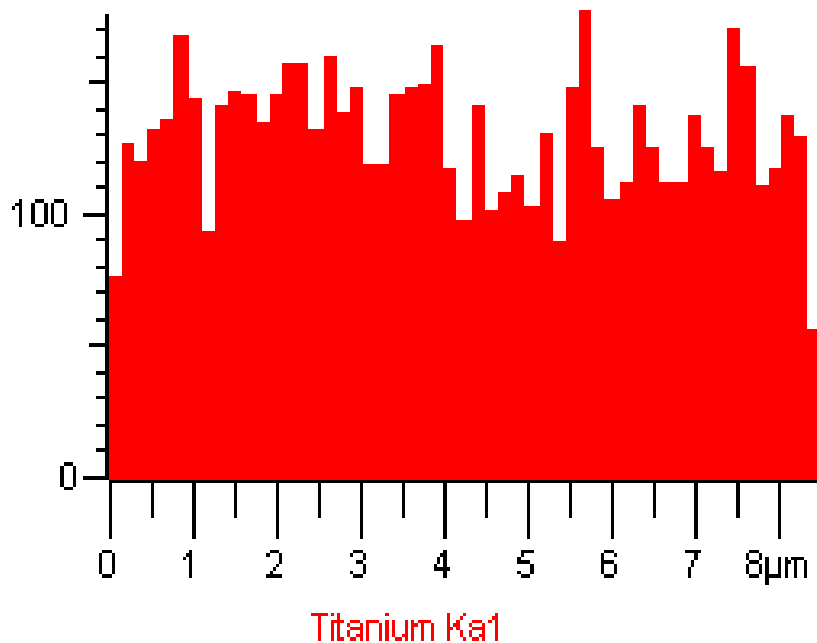


Figure 2: Mapping of Ti atoms distribution along with the ratio of their content

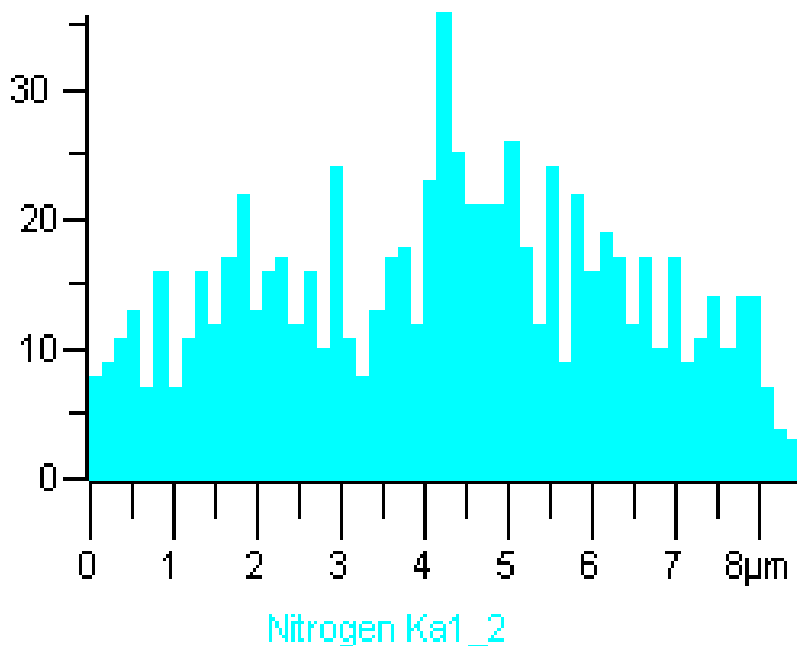


Figure 3: Mapping of N atoms distribution along with the ratio of their content

Figure 3 represents the mapping of N content in TiN coating in the form of histogram showing around 30% of contained area (volume) at the central point of MD shown in Figure 1 (a). This indicates that the area (volume) covered by N atoms in the TiN coating at top front surface not only contained 30% of content but also contained uniform distribution, which is not in the dense manner, but it is in a uniform manner at MD. This indicates that that MD contained approximately three times less concentration of N atoms as compared to Ti atoms.

On incorporating the gas atoms, metallic atoms become poor in conduction where the resulted coatings work as nearly an insulator where enhanced field emission characteristics of propagating photons characteristic current is interrupted, which is the result of non-uniform inter-state electron gap. In this context, the incorporation of N atoms built the bridges through their electron states all around the Ti atoms resulting into lower the propagation of photonic current and further detail regarding inter-state electron gap is given elsewhere [1]. Therefore, the propagation of current no more requires the band gap between conduction band and valence band to explain the science of semiconductor materials or others.

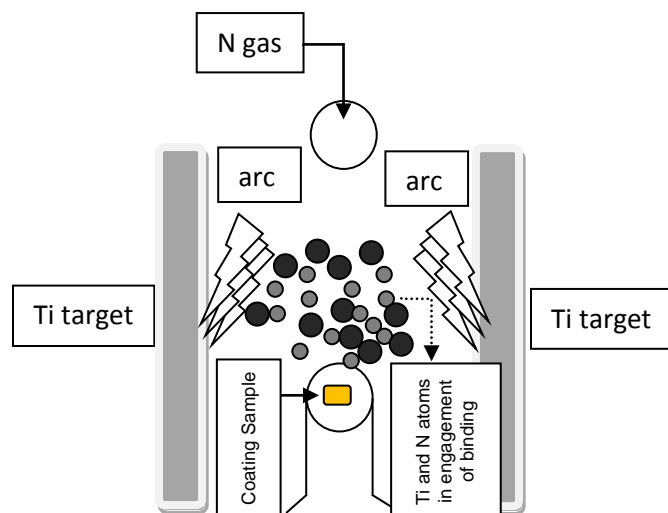


Figure 4: The basic layout of depositing Ti and N as a TiN coating at substrate

At high concentration of N atoms, a random arc is steered for ejecting Ti in atomic form as well as in droplet form depending on the nature of Ti targets along with employed conditions of physical vapor deposition system. In random arc-based PVD system, atoms of Ti (or other metallic nature atoms) are ejected from the surface of

different shaped targets where arc supplied the energy. The basic layout of ejecting Ti atoms and entering N atoms to deposit TiN coating is shown in Figure 4.

In different coating technology deposition-based technologies, regardless of that, required numbers of atoms per unit area or volume are depositing under certain tailored parameters, their dealing of energy is placed under individual attained dynamics, and electron-dynamics is the key to determine certain nature of structure in terms of uniformity in the gaining order. However, it appears that formation of TiN structure in order of any homogeneity is within short range order. Thus, the deposited coatings mainly deal the mixed order of structure of atoms of constituted elements. Each Ti atom only occupies two electrons in the outer ring. This low number of filled states allows the Ti atom to occupy many unfilled states of electrons above east-west poles at both left-side and right-side of North Pole. On the other hand, five filled states of outer ring of each N atom allow less number of unfilled states to occupy outer ring. In this context, a N atom contains several filled states of outer ring. Therefore, those several unfilled states of outer ring in each Ti atom provide provision when it is dealing certain transition state to deal double clamping of energy knots for electrons of filled states of outer ring in the N atom under certain transition state and when it is being placed to its suitable location. Two different nature atoms (Ti and N) develop affinity in terms of strong binding due to intrinsically dealing different nature of forces where non-conservative energy is being involved.

Ti metal is a transition metal, which remains grounded indicating the grounded format force where electrons of filled states remain attempting the gravitation behavior under the expansion of their clamping energy knots in a normal environment possessing ground point at below ground surface. On the other hand, a N atom belongs to gas behavior, which remains in the air indicating the space format force, which is being involved in keeping its ground point at above ground surface. The electrons of N atoms remain attempting the levitation behavior under contraction of clamping energy knots in their normal environment, thus, possessing ground point at above ground surface. Therefore, in their joint deposition under suitable coating technology unit, meant for this job, electrons of N atoms deal affinity in terms of dealing double clamping of unfilled

energy knots of outer ring of Ti atoms. Double clamping of certain electrons of outer ring obey the natural behavior of binding as the atoms of N are searching for ground point at above ground surface while atoms of Ti are also searching for ground point but at below ground surface. While searching their ground points at different levels, they mutually get ready for the common ground point at the surface of depositing substrate. Under the tailored process parameters of their deposition at suitable substrate surface, they deal high adhesion and hard features of resulted coating where maximum number of two differently nature atoms stand for their ordered mid-points, thus, working as hard coating.

The electrons of N atoms deal double clamping of energy knots while focusing to unfilled states of Ti atoms where gas state atoms are uplifting while solid ones are grounding. Obviously, suitable gas state atoms deal double clamping of energy knot to their electrons when they deal the transition state, most probably, a re-crystallization state where approximate angle of electron with respect to clamping energy knot becomes $\sim 35^\circ$ at right-side of normal line in south-pole while attempting the levitation behavior under tickling of clamping energy knot. On approaching such aligned-angle electron of a N atom while forcefully grounding to energy knot of unfilled state of Ti atom uplifting forcefully results into deal double clamping of energy knot; one energy knot of electron belonging to its own and second energy knot (unfilled one) belonging to unfilled state of Ti atom. This double clamping of energy knot to electron of atom (N) grounding forcefully (at substrate surface) under unfilled state of clamping energy knot in Ti atom is shown in Figure 5. While attempting the gravitation behavior of gas atoms where clamping energy knots to electrons expand, the work is being done on the atoms. On the other hand, the work is being done by the atoms of solid behavior where clamping energy knots to electrons contract under levitation behavior. An atom of gas behavior with outer ring and an atom of solid behavior with outer ring are shown in Figure 5 at the instant of dealing double clamping of single electron which set the foundation of science behind hard coating. The inter-changeable force-energy paradigms discussed elsewhere [45] where in addition to describing structure of atoms of various elements, their origin to be in gas state (and to liquid) and to be in solid state (and to liquid) discussed also.

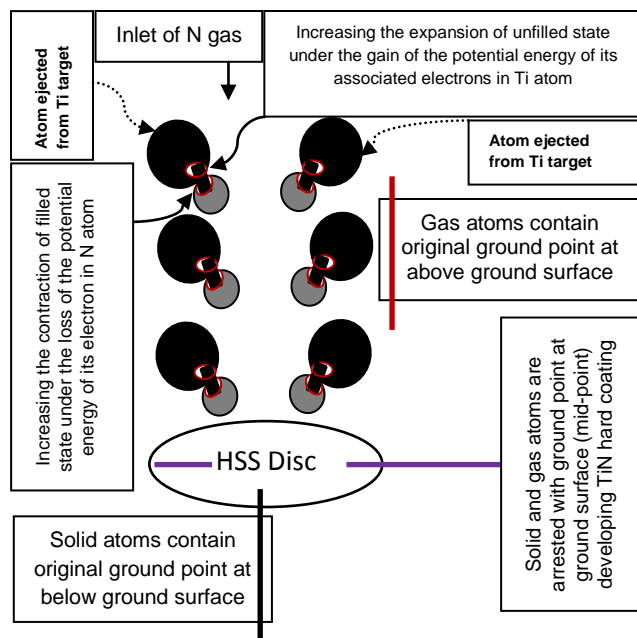


Figure 5: Mechanism of dealing double clamping of electron between two different (opposite force) ground points atoms developing structure of TiN hard coating

Because, solid atom is dealt with the tensing of force of surrounding environment, which is due to the buried ground point under the fully saturated behavior of its electrons in terms of gained potential energy as they deal gravitation behavior at maximum extent. Under conserved manner, nullified levitational force of occupied electrons for each of the transition state of atom releases the tension through dissipating energy, thus, attaining required amount of energy of different transition states of atom does self-work. The level of self-losing potential energy of electrons for each of state of their atom assigns the negative sign. Therefore, in atoms of solid, they do self-work which results into attain their respective states resulting into the contraction of their clamping energy knots having a fixed rate. Further detail is given elsewhere as it has been discussed that this is the contraction and expansion of clamping energy knots to electrons possessing mass (length) more than half at north-side and more than half at south-side determining gas behavior and solid behavior of their atoms, respectively [45]. Some of the detail while studying binding mechanism of different state carbon atoms is also given elsewhere [13] where bringing the gas state carbon atom into solid state carbon atom, the work is being done on that atom through providing the certain shape energy to its electrons. At this instant, the work done is positive. But in the case

of a hard coating both solid atoms and gas atoms deal their opposite phenomena in the description. As, in one case, Ti atoms are reaching to substrate surface where it holds them in the form of deposition. In the second case, N atoms are entering in the middle space of ejecting Ti atoms through dealing the downward force where on instating their original ground point, which is at above ground surface, they are being arrested by the Ti atoms under the mechanism of dealing double clamping of electrons. Therefore, the work is being done by the N atoms as they were restoring their original state from certain transition state, which is under their self-work. Thus, the work done of N atoms remains negative. However, the work done of Ti atoms remains positive as they have gained energy to attain certain transition state where their ground point is not at below ground surface and they are waiting for attaining their ground point at below ground surface. While undertaking those transitions, Ti atoms present the unfilled states of outer rings to clamp suitable electrons of outer rings of N atoms, which are already in the clamp of their own energy knots, thus, formation of Ti-N deals mechanism of double clamping of energy knot to electron under accommodate level of their attained common ground point at just above ground surface or at ground surface of depositing substrate. The mechanism of double clamping of energy knot to electron dealing by many pairs of Ti-N atoms results into develop structure of high hardness as shown in Figure 5.

The similar sort of mechanisms is being anticipated in bi-metallic composition with gas behavior atoms, for example, TiAlN. Again, low measured-hardness coating of chromium nitride (compared to TiN) involves the same mechanism of binding their different nature atoms where high probability is involved as Cr atom contains many unfilled states of outer ring (compared to Ti atom). That's way CrN coating deals low surface roughness as compared to TiN coating [27] because of greater level of homogeneity of binding atoms in evolving their structure. A similar approach may be validated in exploring the science for other very hard, moderate hard and even less hard (soft and porous) coating materials. A different originating science mechanism may be anticipated in the case of TiCN hard coating where involving the same mechanism of double clamping of energy knot to possible electrons of two different metallic nature atoms. Arresting of gas state behavior atoms with metallic behavior atoms endorse the

behavior of force dealing by the electrons under the adjustment of expansion and contraction of clamping energy knots by gaining (increasing) and losing (decreasing) their potential energy, respectively.

4. Conclusions

This is the provision of solid atoms to deal double clamping of energy knots for electrons of gas atoms. The arresting of gas state atoms while the ground point is just at ground surface instead of the ground point at above ground surface decrease the force under the tensing behavior of electrons where their potential energy is being increased under the decrease of contraction of clamping energy knots. The arresting of metallic nature atoms while ground point is just at ground surface instead of ground point at below ground surface increase the force under relaxing behavior where their potential energy is being decreased under the increase of contraction of clamping energy knots. The increase in the expansion of energy knots clamping electrons of atoms of gas state and decrease in the expansion of energy knots clamping electrons of atoms of metallic state enable their affinity through which their developed structure works as a hard coating.

The underlying science of developing hard coating is that atoms of solid behavior deal work against their natural behavior where work done is positive as the atoms work at ground surface (substrate surface) while developing a structure of coating instead of having ground point at below ground surface, whereas, the work done is negative in the case of atoms of gas behavior as they hold ground point at ground surface (substrate surface) instead of at above ground surface while developing a structure of coating. In depositing hard coating, gas atoms engage gravitation behavior of electrons where the expansion of clamping energy knots takes place (on comparative grounds) while solid atoms engage levitation behavior of electrons where the contraction of clamping energy knots takes place (on comparative grounds). This results into deal double clamping of several available electrons of gas behavior atoms through several available unfilled states of solid behavior atoms under the accommodate level of their common ground

points. This results into present the increasing of elastic behavior and the decreasing of plastic behavior along with other characteristics of the resulted hard coating.

Transition metals govern hard features of coating under their affinity to gas behavior atoms because, one is dealing the force of grounded format and other is dealing the force of space format resulting into locate the common ground point having mid-point at ground surface, which is between below ground surface and above ground surface. The electrons of gas atoms (N atoms) depositing on the substrate to evolve structure of TiN coating deal double clamping of energy knots of solid atoms having unoccupied electrons (Ti atoms) from the back side while attempting forcefully the gravitation behavior under their increased potential energy.

The behavior of gas atoms remains alive while arrested by solid behavior atoms. Appropriate vacuum conditions and high power enhance the hardness level of deposited coatings in the form of films. Hard coatings introduce certain properties and application due to the developing of their non-regular structure under non-conservative energy where non-conservative forces are involved. But, they are not overwhelming forever, and lifetime of hard coatings depends on their developing strategies along with the nature of usage. In line with this, deposition of hard coatings along with other ones requires the re-consideration in explaining the science of their structure formation.

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